Supporting Information

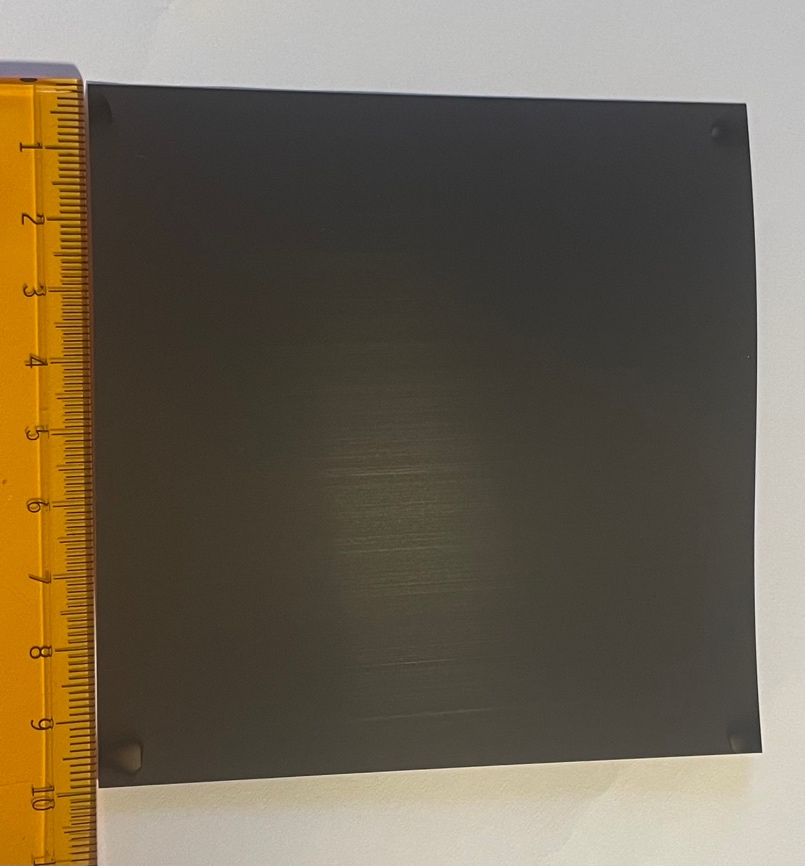
Oxygen defects containing TiN films for the hydrogen evolution reaction: a robust thin film electrocatalyst with outstanding performance

Ayoub Laghrissi and Mohammed Es-Souni \*

A. Laghrissi1  
1Currently with the Technical Faculty, Mads Clausen

Institute, University of Southern Denmark, 6400 Sønderborg

Prof. Dr. habil. M. Es-Souni  
Institute for Materials & Surface Technology,  
Honorary Member, Kiel University of Applied Sciences  
Sokrates Platz 1, D-24149 Kiel, Germany  
E-mail: mohammed.es-souni@fh-kiel.de



**Figure S1**: a photograph of a large area TiNO film deposited on a Ti sheet.

A close up of a graph

Description automatically generated

**Figure S2:** Top view secondary electron (SE) micrographs of TiN (a) and TiN-PdNPs (b) together with their EDS analysis after HER studies.